



Medium fine forming fabric for improved results MultiForm IR

Unique forming fabric design

MultiForm IR is a medium fine forming fabric from the I-Series product line. Based on the successful I-Series weave concept, the forming fabric combines the benefits of a fine paper side on top of a strong and robust bottom side – like no other fabric design before.

Wear side benefits: Improved running times

The robust and engineered wear side of MultiForm IR makes it a very stable and easy-to-guide fabric, which helps to reduce the energy consumption. Moreover, the large amount of available bottom side material ensures excellent running times.

Paper side benefits: Increased runability

The combination of high support points and high open area on top of the robust wear side makes MultiForm IR less sensitive for process variations coming from the stock preparation. The high fiber support ensures good mechanical retention properties and low fiber carry back.

Furthermore, MultiForm IR achieves excellent drainage capacity, a clean run and high first pass retention. Your paper will arrive at the press section with good dryness figures. The design helps on many different positions to extend the operating window of the forming section.

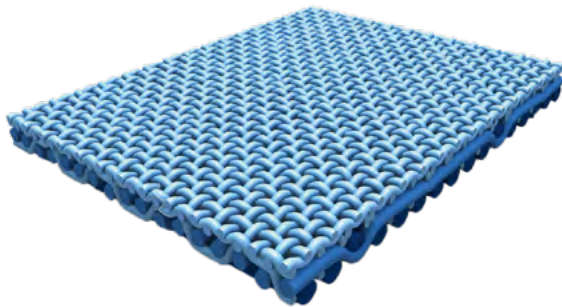
Performance benefits

- High drainage capacity
- High couch solids
- Excellent mechanical retention properties
- High strength properties
- High wear resistance and longer fabric life
- Clean run
- Reduced retention aid consumption
- Excellent formation
- High stability and easy guiding
- Lower energy consumption

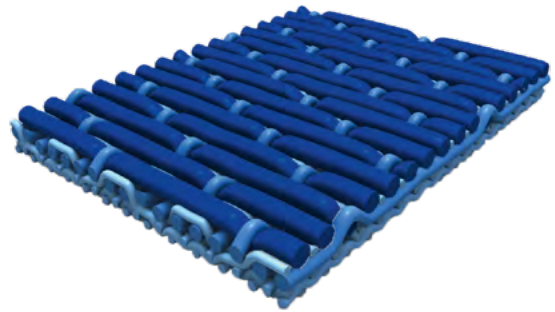
Paper grades and applications

- High-speed gap former packaging machines producing L&F Sackraft
- High-speed and high-quality MultiTable board applications
Gap former
- Hybrid former
- Fourdrinier
- Multi-ply fourdrinier

Fine plain weave 2-shed paper side



Engineered 8-shed wear side



Voith GmbH & Co. KGaA
St. Poeltener Str. 43
89522 Heidenheim, Germany

Contact:
Phone +49 7321 37-0
paper@voith.com
www.voith.com/paper



VOITH
Inspiring Technology
for Generations